

Abstract Submitted  
for the 4CF11 Meeting of  
The American Physical Society

**Photolithography Process using Extreme Ultraviolet LASER** WEI LI, DINESH PATEL, LUCASZ URBANSKI, MARIO MARCONI — We have developed a variety of high-resolution and high-accuracy nanofabrication techniques. They are capable of high resolution nanopatterning on the film of HSQ, which is used as mask later in the pattern transfer. The nanopatterns, which is formed by exposure from 46.9nm table top EUV capillary discharge laser made by CSU, is transferred faithfully down to a gold layer underneath by anisotropic reactive ion etching (RIE) equipment. The equipment has the capability of temperature control and feedback from a thickness monitor. A 10nm error of etching height has been achieved.

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Date submitted: 13 Sep 2011

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